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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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TC 1700

Appl. No. : 09/919,868
Applicant : Yen-Ting Lu
Filed : August 2, 2001
**Title : METHOD FOR REDUCING LINE EDGE
ROUGHNESS OF PATTERNED PHOTORESIST**
Examiner : YOUNG, CHRISTOPHER G
Docket No. : 4425-168

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

In response to the Official Action mailed June 27, 2003, Applicant submits herewith an RCE and respectfully amends the application according to the Official Action.

Please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begin on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.